# Development of Radiation Hard Sensors for Very High Luminosity Colliders - CERN-RD50 project -

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## **On behalf of CERN RD50 Collaboration**

**Complete author list at http://www.cern.ch/rd50** 

LHC:  $\mathscr{L} = 10^{34} \text{ cm}^{-2} \text{s}^{-1}$ 10 years operationfluence of fast hadrons : $\phi(R = 4 \text{ cm}) \sim 3 \cdot 10^{15} \text{ cm}^{-2}$ 

**Possible LHC upgrade ("Super-LHC"):**  $\mathscr{L} = 10^{35} \text{cm}^{-2} \text{s}^{-1}$ 5 years operation

**Anticipated Radiation Environment** (CERN-TH/2002-078)

Radius (cm)	Fluence of fast hadrons [cm <sup>-2</sup> ]	Dose [kGy]	
4	1.6x10 <sup>16</sup>	4200	
22	8.0x10 <sup>14</sup>	350	
115	$1.0 \times 10^{14}$	9.3	

Present semiconductor detector technology is not able to operate at such high fluences/doses

## RD50 - Development of Radiation Hard Semiconductor Devices for High Luminosity Colliders 280 Members from 55 Institutes

## **Main Objective**

Development of ultra-radiation hard semiconductor detectors, able to withstand fast hadron fluences and doses as expected for luminosity upgrade of the LHC to  $10^{35}$  cm<sup>-2</sup>s<sup>-1</sup>.

47 European and Asian institutes (34 west, 11 east)

Belgium (Louvain), Czech Republic (Prague (2x)), Finland (Helsinki (2x), Oulu), Germany (Berlin, Dortmund, Erfurt, Halle, Hamburg, Karlsruhe), Greece (Athens), Italy (Bari, Bologna, Florence, Milano, Modena, Padova, Perugia, Pisa, Trento, Trieste, Turin), Lithuania (Vilnius), Norway (Oslo (2x)), Poland (Warsaw), Romania (Bucharest (2x)), Russia (Moscow (2x), St.Petersburg), Slovenia (Ljubljana), Spain (Barcelona, Valencia), Sweden (Lund) Switzerland (CERN, PSI), Ukraine (Kiev), United Kingdom (Exeter, Glasgow, Lancaster, Liverpool, London, Sheffield, University of Surrey)

7 North-American institutes Canada (Montreal), USA (Fermilab, Purdue University, Rutgers University, Syracuse University, BNL, University of New Mexico )

1 Middle East institute Israel (Tel Aviv) **Detailed member list:** http://cern.ch/rd50

## **RD50 - Scientific objectives and strategies**

### **Three R&D strategies:**

- Material engineering
  - Defect engineering of silicon (oxygenation, dimers, ...)
  - New detector materials (SiC, ...)
- Device engineering
  - Improvement of present planar detectors
    - (3D detectors, thin detectors, cost effective detectors,...)
- Variation of detector operational conditions
  - Low temperature operation
  - Forward bias operation

## **Further key tasks:**

- Basic studies
- Defect modeling and device simulation

RD50 Center of gravity

#### Scientific Organization of RD50



#### **Macroscopic Radiation Damage**

1. Change of  $V_{dep}$ ,  $N_{eff}$  and annealing behavior



#### 2. Increase of leakage current and annealing behaviour



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#### **3.** Deterioration of the charge collection efficiency



## **Defect Engineering of Silicon**

**Impurities incorporation to prevent the formation of divacancy related defects** 

 $\rightarrow$  Oxygen can getter vacancies reducing the formation of deeper levels as V<sub>2</sub>O

 $V < VO \longrightarrow VO$  (not harmful at room temperature)  $V < VO \longrightarrow V_2O$  (negative space charge)





Benefit with gamma and 24GeV/c protons in terms of β. No benefit with neutrons.

## **Different kind of Si materials investigated by RD50**

Material	Symbol	ρ Ω cm	[ <b>O</b> <sub>i</sub> ] cm <sup>-3</sup>
Standard n- or p-type FZ	STNFZ	$1-7 \cdot 10^{3}$	< 5 10 <sup>16</sup>
Diffusion Oxygenated FZ p or n-type	DOFZ	$1-7 \cdot 10^{3}$	$\sim 1-2  10^{17}$
Epi-layer 50 μm on CZ n-type ITME	EPI	50-100	substrate: 1 · 10 <sup>18</sup>
Czochralski Sumitomo, Japan	CZ	$1.2 \cdot 10^{3}$	$\sim 8-9 \ 10^{17}$
Magnetic Czochralski Okmetic Finland	MCZ	$1.2 \cdot 10^{3}$	~ <b>5-9</b> 10 <sup>17</sup>

- Microscopic study of radiation induced defects
- Changes in the macroscopic parameters of single pad detectors
- Performance of segmented devices

#### **Microscopic study of radiation induced defects**

#### Interpretations for the V<sub>2</sub>O energy level structure

- "I defect" Acceptor + Donor  $E_c$  0.545 eV +  $E_v$ +0.23 eV induced by irradiation [I.Pintilie et al., APL 82 (13), 2169 (2003)]
- "X-defect" Double-acceptor E<sub>c</sub>-0.467

 $E_c-0.467eV + E_c-0.233eV$  irradiation + annealing of  $V_2$ [E.Monakhov et al., PRB 65(2002)233207]



I defect responsible for type inversion in Standard FZ Si after <sup>60</sup>Co γ–irradiation and for increase of leakage current with dose. It appears in oxygen lean Si.

# Presence of a bistable donor which overcompensate radiation induced deep acceptors



## Macroscopic Effects: recent results on Czochralski Si

190 MeV  $\pi$  irradiation Villigen Cz from Sumitomo Sitix, Japan 24 GeV/c p irradiation CERN Cz from Sumitomo Sitix, Japan



- No type inversion (SCSI)
- Reverse current and charge trapping comparable to FZ silicon

## 10-30 MeV proton Jyväskylä, Finland Magnetic Cz-Si Okmetic, Finland Improvement in V<sub>dep</sub>, N<sub>eff</sub> Observed SCSI Reduction of reverse current ??

900 MeV electron Elettra (Trieste, Italy) CZ-Si Sumitomo Japan, EPI-ITME

**Decrease of CCE observed only beyond 10<sup>15</sup> ecm<sup>-2</sup> for CZ and EPI** 



#### **New Materials: Silicon Carbide and GaN**



## **Epitaxial SiC Schottky Barriers**



- $\blacklozenge$  n epilayer  $N_{eff}$  ~5×10^{13} cm^{-3} 40µm by IKZ Berlin on CREE substrate
- Schottky and Ohmic contacts produced by Alenia System
- $\blacklozenge$  Charge collection efficiency tested with  $\alpha s$   $^{241}Am$  and  $\beta$   $^{90}Sr$
- Irradiation tests with 24GeV proton in progress

Q~2200e corresponding to CCE 100% at V<sub>dep</sub>= 60V



#### **Proton-irradiation induced defects in epitaxial 4H-SiC Schottky Barriers**

Research activity by the group of Bologna in collaboration with Torino

- n epilayer 7µm
- $N_{\rm eff} \sim 7 \times 10^{15} {\rm cm}^{-3}$
- Schottky Barriers Ti or Ni
- Ohmic contacts Ti/Ni/Ag
- Deep levels by C-DLTS
- ♦ 6.5MeV p up to 6.4x10<sup>13</sup>cm<sup>-2</sup>

Six traps detected

◆ E = 0.18 - 1.22eV

•  $s = 10^{-13} - 10^{-18} cm^{-2}$ 

•  $N_t = 10^{11} - 5 \times 10^{14} \text{ cm}^{-3}$ 



The creation of energy levels with  $N_t$  of the same order of magnitude of the doping density does not affect the charge transport in the detector. This probably due to the shallow energies of the traps.

### **2. SiC Triode Detector structures**

#### Produced and tested at Ioffe Physico-Technical Institute, St. Petersburg, Russia

• Development of radiation-hard triode (transistor) detector structures based on SiC layers. Triode detector to get amplification of a charge generated in the detector bulk and realize the gain of the detector signal compared to that in the diode structure.

 p-type epilayer SiC grown by sublimation epitaxy on n<sup>+</sup> SiC wafers: 6H-SiC (processed at Ioffe Institute) 10μm 4H-SiC (processed in Linkoping University, Sweden) 30μm

Emitter: n+ SiC waferBase: p+ epi-layerCollector: Schottky barrier

• Irradiation at Ioffe Institute with 8 MeV protons up to 10<sup>13</sup>-10<sup>14</sup>cm<sup>-2</sup>, corresponding to 10<sup>16</sup>cm<sup>-2</sup> 1GeV protons

• Charge collection efficiency investigated with  $\alpha$ -particles  $E_{\alpha} = 3.5 - 5.45 \text{MeV}$ 

Material	6H-SiC	4H-SiC
Fluence [cm <sup>-2</sup> ] and particle	2.10 <sup>13</sup> 8MeV protons	10 <sup>14</sup> 8MeV protons
Eq Fluence [cm <sup>-2</sup> ] 1 GeV proton	$1.3 \cdot 10^{15}$	$1.10^{16}$
thickness of the epilayer [µm]	10	30
$N_{\rm eff}(0)  [\rm cm^{-3}]$	$7.5 \cdot 10^{14}$	$(3-5) \cdot 10^{15}$
$N_{eff}(\Phi) [cm^{-3}]$	$1.8-2.6 \cdot 10^{13}$	
V <sub>dep</sub> (0) [V]	125	8500
$V_{dep}(\Phi)$ [V]	2.5	
Gain at V <sub>dep</sub>	18	Not achieved
α-particle energy	3.5MeV	5.5 MeV
CCE % after irradiation	~ 100 %	~ 80 %

#### Results on Triode epitaxial SiC Detector after irradiation with 8 MeV p up to 10<sup>14</sup>cm<sup>-2</sup>

Data From E. Verbitskaya et al.



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#### **3.** SiC p<sup>+</sup>n junction detectors

**Research activity of the Perugia group in collaboration with Florence, IMM-CNR Bologna and INSA-CEGELY, Lyon France** 



#### **Semi-Insulating SiC detectors**

Research activity of Glasgow, Surrey, Vilnius. Bulk SiC has incomplete charge collection (no e transport) and suffers for polarisation effects (traps e.g. Vanadium and micropipes)



Simulated CCE of bulk and epi devices up to fluences of 10<sup>16</sup> cm<sup>-2</sup> in talk N33-3 by Tina Quinn et al.

Data from M. Rahman et al.

### **Semi-Insulating GaN detectors**

#### Research activity of Vilnius, Glasgow, Surrey

- SI-GaN epitaxial layer on n-type GaN substrate (University of Tokushima Japan)
- Au Schottky contacts 1.5 mm diameter
- Charge Collection tested with α-particles <sup>241</sup>Am by Glasgow, Surrey groups
- Irradiated by X rays 600MRad
- Irradiated by neutrons in Ljubljana up to 5x10<sup>14</sup>cm<sup>-2</sup>

SI-GaN	Energy	Fluence	CCE %
Non-Irradiated			92
Irradiated by X-rays	10keV	600MRad	100
Irradiated by neutrons	100keV	$5 \times 10^{14} \text{cm}^{-2}$	77

#### Future work: study thicker SI-GaN epilayers

# GaN IBIC images GaN IBIC images show charge transport only under contact pad Excellent uniformity of signal with no field enhancement at edges Contact is mainly obscured by silver dag bond wire

#### See P. Sellin and J. Vaitkus talks at 2<sup>nd</sup> RD50 workshop

www.cern.ch/rd50

### **Device Engineering: 3D and Semi3D detectors**

- Semi 3-d devices, proposed by Z. Li, BNL, made in collaboration with US groups
- 3-d devices, proposed by S. Parker.
- Holes processing: dry etching, Laser drilling, Photo electrochemical. Present aspect ratio (within RD50) 13:1, target > 30:1

Some result ( $\alpha$  spectroscopy) before and after 10<sup>14</sup> 300 MeV/c  $\pi$  cm<sup>-2</sup>



Data from P. Roy, 2<sup>nd</sup> RD50 workshop

# Very promising silicon devices for speed and radiation hardness.

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## **Device engineering: Thin SiC detectors by micromachining**

The active thickness of the device after heavy irradiation is limited by the effective drift lengths e: ~150μm, h:~50μm after 1MeV neutron irradiation at 10<sup>15</sup>cm<sup>-2</sup> (Kramberger et al.).

Thin Si detectors 50-100 $\mu$ m: low V<sub>dep</sub>, limited leakage current Two technical Approaches:

- Thinning by micromachining: research activity of the IRST-Trento group in collaboration with the other italian groups.

IRST-Trento: SEM of a silicon wafer thinned by TMAH

Leakage Current [nA/cm <sup>3</sup> ]	V <sub>dep</sub> [V]
80	12
30	~1
55	<1
	Leakage Current [nA/cm <sup>3</sup> ] 80 30 55

Ready to be irradiated.

- Epitaxial Si detectors: wafers by ITME, processed by CiS, now irradiated up to 9.2410<sup>15</sup> 24GeV p/cm<sup>2</sup> at CERN, measurements (Hamburg group) in progress.



Cross section of a thinned silicon detector by IRST-Trento



## Talks of RD50 group members at IEEE 2003 NSS and RTSD

N4-5 Super radiation hard technologies: 3D and widegap detectors M.Rahman et al. N20-6 Measurement of the Trapping Time constants in proto-irradiated, Si .... O. Krasel et al. N20-4 Radiation damage in bipolar transistors caused by thermal neutrons, I. Mandic et al. N26-17 Lithium Ion Irradiation effects on diodes manufactured on epitaxial Si, A.Candelori et al. N26-20 Radiation damage tests of all-p type termination structures .... C. Piemonte et al. N26-21 An enhanced device simulation of heavily irradiated silicon ... F. Moscatelli et al. N26-22 TSc analysis of gamma irradiated standard and oxygenated diodes ... D. Menichelli et al. N33-2 Radiation Hardness of high resistivity CZ Si detectors after gamma.... Z. li et al. N33-3 Comparison of Bulk and Epitaxial 4H-SiC detectors T. Quinn et al. N36-117 Single Neutron pixel detectors based on medipix-1 Device, I.Iakubek et al. R15-2 On the physical processes induced by particle irradiation ... by A.Cavallini et. R18-4 Perfomance of Silicon Carbide Radiation Detectors, F. Nava et al.

# **Summary**

RD50: Development of Ultra Radiation Hard semiconductor detectors for Super LHC. Promising results have been obtained:

• Radiation hardening by defect engineering: reduction of  $N_{eff}$  at high fluences of fast hadrons and gamma doses using oxygen enriched Si ( DOFZ, Cz, MCz, epitaxial)

• SiC and GaN  $\rightarrow$  good charge collection properties but thicker layers required to be competitive with Si

♦ 3-D detectors: promise of radiation hardness ( $\sim 10^{14}$  p/cm<sup>2</sup>), improvement of aspect ratio, electrodes in progress

device engineering by thinning, edge-less detectors, semi-3d: projects running

◆ Irradiations at very high doses ( 10<sup>16</sup>cm<sup>-2</sup>) of single pad and segmented devices in progress